

**CERTIFICATE OF MAILING BY FIRST CLASS MAIL (37 CFR 1.8)**

Applicant(s): Masato NISHIKAWA et al.

Docket No.

2003JP307

Serial No.

10/550,110

Filing Date

September 19, 2005

Examiner

EGWIM, Kelechi Chidi

Group Art Unit

1796

Invention: AUXILIARY FOR FORMING FINE PATTERN AND PROCESS FOR PRODUCING THE SAME

I hereby certify that this English Language Abstract of JP 10-120968 A - 2 Pages

(Identify type of correspondence)

is being deposited with the United States Postal Service as first class mail in an envelope addressed to: The

Commissioner of Patents and Trademarks, Washington, D.C. 20231-0001 on November 20, 2008

(Date)

MARIA T. SANCHEZ

(Typed or Printed Name of Person Mailing Correspondence)

A handwritten signature in cursive script, appearing to read "Maria T. Sanchez".

(Signature of Person Mailing Correspondence)

Note: Each paper must have its own certificate of mailing.

# PATENT ABSTRACTS OF JAPAN

(11)Publication number : 10-120968

(43)Date of publication of application : 12.05.1998

(51)Int.Cl.

C09D141/00  
C09D129/04  
C09D129/10  
C09D131/04  
C09D133/02  
C09D139/06  
C09D171/02  
C09D201/00  
G03F 7/11  
H01L 21/027

(21)Application number : 09-210282

(71)Applicant : HITACHI CHEM CO LTD

(22)Date of filing : 05.08.1997

(72)Inventor : NISHIO SHIGERU

KATO KOJI

HASHIMOTO MASAHIRO

HASHIMOTO MICHIAKI

(30)Priority

Priority number : 08226193    Priority date : 28.08.1996    Priority country : JP

(54) RESIN COMPOSITION FOR RESIST PROTECTION FILM, RESIST PROTECTION FILM AND PATTERN PRODUCING METHOD USING THE FILM

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a resin composition for a resist protection film effective for suppressing PED effect and free from absorption band up to ultraviolet range having short wavelength, to provide a resist protection film made of the composition and to provide a process for producing a pattern having high dimensional accuracy in high workability.

SOLUTION: This resin composition for resist protection film and the resist protection film made thereof contain a polyvinylsulfonic acid compound, a water-soluble polymer and water. The pattern-forming process comprises a step to form a resist film on a substrate, a step to expose the resist film in the form of a prescribed pattern and a step to develop the exposed resist. In the above case, a resist protection film is formed on the resist film before the exposure using the composition for resist protection film.

LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration],

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2003 Japan Patent Office